ABSTRACT OF THE DISCLOSURE

Disclosed herein is a method of forming a negative pattern of carbon nanotubes through: modifying the surfaces of carbon nanotubes to have double bond-containing functional group capable of participating in radical polymerization; coating a substrate with a liquid coating composition prepared by dispersing the surface-modified carbon nanotubes in an organic solvent along with a photoinitiator; exposing the film to UV light through a photomask to induce radical polymerization of the carbon nanotubes; and developing the film. By virtue of the present invention, desired patterns of carbon nanotubes can be easily made on the surfaces of various substrates according to the conventional photolithography procedure.